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2/1/03PATENT
Docket No. 150.00560102IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Applicant(s):	Lee et al.)	Group Art Unit:	1765
)		
Serial No.:	09/560,268)	Examiner:	Duy Deo
Confirmation No.:	2517)		
)		
Filed:	April 26, 2000)		
)		
For:	COMPOSITIONS FOR SELECTIVELY ETCHING AGAINST COBALT SILICIDE (As Amended)			

RESPONSE UNDER 37 CFR § 1.116

Assistant Commissioner for Patents
BOX AF
Washington D.C. 20231

Dear Sir:

The following is provided in response to the Final Office Action mailed December 4, 2002. No claims have been amended or added. Claims 64-65 and 67-95 are pending. Reconsideration and withdrawal of the rejections are respectfully requested in view of the following remarks.

The 35 U.S.C. § 102(e) Rejection

The Examiner rejected claims 68-70, 72-75, 77-81, 83-86, 88-91, and 93 under 35 U.S.C. § 102(e) as being anticipated by Shiramizu (U.S. Patent No. 6,116,254).

Applicants traverse these rejections and submit that claims 68-70, 72-75, 77-81, 83-86, 88-91, and 93 are not anticipated by Shiramizu for at least the following reasons. For a claim to be anticipated under 35 U.S.C. § 102(e), each and every element of the claim must be found in a single prior art reference. *See* M.P.E.P. § 2131.

Claims 68-70, 72-75, 77-81, 83-86, 88-91, and 93 are not anticipated by Shiramizu because such reference does not teach each and every element of claims 68-70, 72-75, 77-81, 83-86, 88-91, and 93. For example, each of independent claims 68, 73, 77, 79, 84, and 89 recite that the claimed etching compositions include a specified etch rate. Claims 68 and 84 recite that the

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